제 31회 한국반도체학술대회 The 31st Korean Conference on Semiconductors

2024년 1월 24일(수)-26일(금) | 경주화백컨벤션센터(HICO)

2024년 1월 26일(금), 15:40-17:25 Room B(102),1층

H. Display and Imaging Technologies 분과

[FB3-H] Display and Imaging Technologies V

좌장: 권혁인 교수(중앙대학교)

FB3-H-1 15:40-15:55	Partially Transparent Flexible IGZO TFT with PEDOT:PSS Gate and
	Parylene-C Gate Dielectric Yoojeong Ko and Dong-Wook Park University of Seoul
	Extracting Bulk Trap Density of Oxide Semiconductor Thin Films Using
	Space Charge Limited Current
FB3-H-2	Changeon Jin ¹ , Taewon Seo ¹ , and Yoonyoung Chung ^{1,2,3}
15:55-16:10	¹ Department of Electrical Engineering, POSTECH, ² Department of Semiconductor
	Engineering, POSTECH, ³ Center for Semiconductor Technology Convergence, POSTECH
	Fabrication and Applications of a-ITZO Charge-Trapping TFTs Using
FB3-H-3	AI_2O_3 and HfO_2 in Memory-In-Pixel Display Technology
16:10-16:25	Seoungmin Park ¹ , Taehyeon Noh ¹ , Youngyeong Lee ² , and Younghyun Kim ¹
	¹ Department of Photonics and Nanoelectronics, BK21 FOUR ERICA-ACE Center,
	Hanyang University, ² HANA Optronic, Inc.
	Controllable, Large Gamut Sensitivity for Stretchable Strain Sensors
FB3-H-4	With One Dimensional Single Walled Carbon Nanotubes
16:25-16:40	Hyeonbin-Jo, Yujin Choi, Taeho Kang, Gyubeen Kim, and Sung Hun Jin
	Department of Electronic Engineering, and I-Nanofab Center, Incheon National University
FB3-H-5	Ambipolar Organic Inverter based on Non-fullerene Acceptor
16:40-16:55	Seungyeon Koh, MiRiNae Lee, HwaPyeong Noh, Swarup Biswas, and Hyeok Kim
10.40-10.55	School of Electrical and Computer Engineering, University of Seoul
FB3-H-6 16:55-17:10	Low-hydrogen SiO _x N _y Thin Film via Plasma-enhanced Atomic Layer
	Deposition Using a Hydrogen-free Silicon Precursor and N_2 Plasma :
	Growth Mechanism and Dielectric Properties
	Chae-Yeon Park ¹ , Hae Lin Yang ¹ , Tae-Yeon Kim ¹ , Gi-Beom Park ¹ , Ara Yoon ¹ ,
	Jongryul Park ² , Taehyeong Kang ^{2,3} , Yongjoo Park ³ , and Jin-Seong Park ¹
	¹ Division of Materials Science and Engineering, Hanyang University, ² SK Trichem
	Co., Ltd.

제 31회 한국반도체학술대회 The 31st Korean Conference on Semiconductors

2024년 1월 24일(수)-26일(금) | 경주화백컨벤션센터(HICO)

FB3-H-7 17:10-17:25	Copper-lodide Film Formation via Physical Vapor Deposition Method
	and Their Electrical Contact and Sheet Resistance Properties
	Geun Lee, Da Han Lee, Tae Ho Kang, Tae Won Jin, Woo In Kim, and Sung Hun Jin
	Department of Electronic Engineering, and I-Nanofab Center, Incheon National
	University